Li, Jiapeng

List of Publications by Year in descending order

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840776 940533 304 28 11 16 h-index citations g-index papers 29 29 29 192 docs citations times ranked citing authors all docs

| # | Article | IF | CITATIONS |
|----|--|-----|-----------|
| 1 | A Comparative Study on Fluorination and Oxidation of Indium–Gallium–Zinc Oxide Thin-Film Transistors. IEEE Electron Device Letters, 2018, 39, 196-199. | 3.9 | 37 |
| 2 | High-performance and reliable elevated-metal metal-oxide thin-film transistor for high-resolution displays. , $2016, \ldots$ | | 33 |
| 3 | Elevated-Metal Metal-Oxide (EMMO) Thin-Film Transistor: Technology and Characteristics. IEEE Electron Device Letters, 2016, , 1-1. | 3.9 | 30 |
| 4 | Fluorination-Enabled Monolithic Integration of Enhancement- and Depletion-Mode Indium-Gallium-Zinc Oxide TFTs. IEEE Electron Device Letters, 2018, 39, 692-695. | 3.9 | 25 |
| 5 | A Comparative Study on the Effects of Annealing on the Characteristics of Zinc Oxide Thin-Film Transistors With Gate-Stacks of Different Gas-Permeability. IEEE Electron Device Letters, 2014, 35, 841-843. | 3.9 | 24 |
| 6 | An oxidation-last annealing for enhancing the reliability of indium-gallium-zinc oxide thin-film transistors. Applied Physics Letters, 2017, 110 , . | 3.3 | 24 |
| 7 | Characteristics of Elevated-Metal Metal-Oxide Thin-Film Transistors Based on Indium-Tin-Zinc Oxide. IEEE Electron Device Letters, 2017, 38, 894-897. | 3.9 | 19 |
| 8 | Resilience of Fluorinated Indium-Gallium-Zinc Oxide Thin-Film Transistor Against Hydrogen-Induced Degradation. IEEE Electron Device Letters, 2020, 41, 729-732. | 3.9 | 17 |
| 9 | A Physical Model for Metal–Oxide Thin-Film Transistor Under Gate-Bias and Illumination Stress. IEEE Transactions on Electron Devices, 2018, 65, 142-149. | 3.0 | 15 |
| 10 | A Bottom-Gate Metal–Oxide Thin-Film Transistor With Self-Aligned Source/Drain Regions. IEEE Transactions on Electron Devices, 2018, 65, 2820-2826. | 3.0 | 15 |
| 11 | Pâ€15: The Use of Fluorination to Enhance the Performance and the Reliability of Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistors. Digest of Technical Papers SID International Symposium, 2018, 49, 1235-1238. | 0.3 | 14 |
| 12 | Thermally Induced Variation of the Turn-ON Voltage of an Indium–Gallium–Zinc Oxide Thin-Film Transistor. IEEE Transactions on Electron Devices, 2015, 62, 3703-3708. | 3.0 | 13 |
| 13 | Self-Aligned Elevated-Metal Metal-Oxide Thin-Film Transistors for Displays and Flexible Electronics. , 2019, , . | | 11 |
| 14 | Fluorinated indiumâ€galliumâ€zinc oxide thinâ€film transistor with reduced vulnerability to hydrogenâ€induced degradation. Journal of the Society for Information Display, 2020, 28, 520-527. | 2.1 | 10 |
| 15 | Three-Mask Elevated-Metal Metal-Oxide Thin-Film Transistor With Self-Aligned Definition of the Active Island. IEEE Electron Device Letters, 2018, 39, 35-38. | 3.9 | 5 |
| 16 | 24â€2: Distinguished Student Paper: Fluorination for Enhancing the Resistance of Indiumâ€Galliumâ€Zinc Oxide Thinâ€Film Transistor against Hydrogenâ€Induced Degradation. Digest of Technical Papers SID International Symposium, 2020, 51, 347-350. | 0.3 | 3 |
| 17 | 8.1: <i>Invited Paper:</i> Enhanced Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistor Technology. Digest of Technical Papers SID International Symposium, 2018, 49, 75-78. | 0.3 | 2 |
| 18 | Pâ€11: Carrier Concentration Reduction by Fluorine Doping in Pâ€Type SnO Thinâ€Film Transistors. Digest of Technical Papers SID International Symposium, 2019, 50, 1251-1254. | 0.3 | 2 |

| # | Article | IF | CITATIONS |
|----|---|-----|-----------|
| 19 | A Timing Model for the Optimal Design of a Prototype Active-Matrix Display. IEEE Transactions on Electron Devices, 2020, 67, 3167-3174. | 3.0 | 2 |
| 20 | Pâ€1.5: Edge Effects of Threeâ€Mask Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistor and Their Elimination. Digest of Technical Papers SID International Symposium, 2018, 49, 531-534. | 0.3 | 1 |
| 21 | 1.3: A Timing Model for the Design of an Activeâ€Matrix Display. Digest of Technical Papers SID International Symposium, 2019, 50, 13-16. | 0.3 | 1 |
| 22 | Pâ€4: Enhanced Scalability and Reliability of High Mobility Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistors with Bandgap Engineering. Digest of Technical Papers SID International Symposium, 2020, 51, 1322-1325. | 0.3 | 1 |
| 23 | Elevated metal metal-oxide thin-film transistor — A new bottom-gate transistor architecture for flat-panel displays. , 2016, , . | | 0 |
| 24 | Pâ€1.4: Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistor with Fluorinated Indiumâ€Galliumâ€Zinc Oxide Channel towards Flexible Applications. Digest of Technical Papers SID International Symposium, 2018, 49, 528-530. | 0.3 | 0 |
| 25 | 24.3: Shortâ€Channel Indiumâ€Galliumâ€Zinc Oxide Thinâ€Film Transistor Enabled by Thermal Dehydrogenation and Oxidizing Defectâ€Suppression. Digest of Technical Papers SID International Symposium, 2018, 49, 255-258. | 0.3 | 0 |
| 26 | Pâ€21: Threeâ€Mask Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistor Technology for Highâ€Resolution AMOLED Application. Digest of Technical Papers SID International Symposium, 2018, 49, 1256-1259. | 0.3 | 0 |
| 27 | 8.2: <i>Invited Paper:</i> Elevatedâ€Metal Metalâ€Oxide Thinâ€Film Transistor with Selfâ€Aligned Source/Drain Regions. Digest of Technical Papers SID International Symposium, 2019, 50, 75-78. | 0.3 | 0 |
| 28 | Systematic Defect Manipulation in Metal Oxide Semiconductors towards High-Performance Thin-Film Transistors. , 2020, , . | | 0 |